

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
)
Mari INOUE) Parent Group Art Unit: 2813
)
1.53(b) Divisional of Application) Parent Examiner: C. Thompson
10/107,247, filed March 28, 2002)
)
Filed: Herewith)
)
For: A METHOD FOR CORRECTING A)
DESIGN DATA OF A LAYOUT
PATTERN OF A PHOTOMASK,
PHOTOMASK MANUFACTURING
BY SAID METHOD, AND
SEMICONDUCTOR DEVICE
METHOD USING SAID
PHOTOMASK

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)

Pursuant to 37 C.F.R. §§ 1.56 and 1.97(b), applicant brings to the attention of the Examiner the documents listed on the attached PTO 1449. This Information Disclosure Statement is being filed within three months of the filing date of the above-referenced application.

Copies of the listed documents were previously submitted in a prior application, application no. 10/107,247, filing date March 28, 2002, upon which applicant relies for the benefits provided in 35 U.S.C. § 120, or cited by the Examiner.

Applicant respectfully requests that the Examiner consider the listed documents and indicate that they were considered by making appropriate notations on the attached form.

This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that each or all of the listed documents are material or constitute "prior art." If the Examiner applies any of the documents as prior art against any claim in the application and applicant determines that the cited documents do not constitute "prior art" under United States law, applicant reserves the right to present to the office the relevant facts and law regarding the appropriate status of such documents.

Applicant further reserves the right to take appropriate action to establish the patentability of the disclosed invention over the listed documents, should one or more of the documents be applied against the claims of the present application.

If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,
GARRETT & DUNNER, L.L.P.

Dated: November 3, 2003

By: Richard V. Burgujian Reg. 24,014
for Reg. No. 31,744

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INFORMATION DISCLOSURE CITATION

Atty. Docket No.	04329.2802-01	Appln. No.	n/a
Applicant	Mari INOUE		
Filing Date	November 3, 2003	Group:	n/a

U.S. PATENT DOCUMENTS

Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
	4,499,595	02-1985	Masaitis et al.			

FOREIGN PATENT DOCUMENTS

Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
2000-75467	3/14/00	Japan			Abstract
2000-20564	01/21/00	Japan			Abstract
7-297252	11/10/95	Japan			Abstract

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	Int'l Sematech "Advanced Process Control Framework Initiative Project Overview" June 30, 1999 Technology Transfer No. 99053735A-TR http://www.sematech.org/public/docubase/document/3735atr.pdf visited 4/4/2003
	Kotani et al., "Highly Accurate Process Proximity Correction Based on Empirical model for 0.18 μ m Generation and Beyond", Jpn. J. Appl. Phys. Vol. 38 (1999), pp. 6957-6962, Part 1, No. 12B, December 1999.
	Takahashi et al., "Performance of JBX-9000MV with Negative Tone Resist for 130 nm Reticle", 20 th Annual BACUS Symposium on Photomask Technology, Vol. 4186, pp. 22-33, XP008020520, Proceedings of SPIE Vol. 4186 (2001).

INFORMATION DISCLOSURE CITATION

Atty. Docket No.	04329.2802-01	Appln. No.	n/a
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Examiner	Date Considered		
*Examiner:	Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.		
Form PTO 1449	Patent and Trademark Office - U.S. Department of Commerce		